

VIA EFS

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Patent Application:	Luca Pusterla, et al.	§	
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Conf. No.:	7623	§	Group Art Unit: 1743
		§	
Appln. No.:	10/601,383	§	Examiner: Yelena G. Gakh
		§	
Filing Date:	June 23, 2003	§	Atty. Docket No.: 6023-169US
		§	(BX2453M)
Title:	METHOD FOR MEASURING THE CONCENTRATION OF IMPURITIES IN HELIUM BY ION MOBILITY SPECTROMETRY		

AMENDMENT

This is in response to the Office Action dated December 1, 2006 (Paper No. 20061027) in the above-identified patent application. This response is being timely filed by March 1, 2007.

Please amend the application, without prejudice, as follows: